

DOCKET NO.: 0160-0193-0 PCT/hyc

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

IN RE APPLICATION OF: Hiroshi IKEDA, et al.

SERIAL NUMBER: 09/463,961

GROUP: 1754

FILED: March 9, 2000

EXAMINER: Wayne A. LANGE

FOR: PROCESS AND APPARATUS FOR TREATING SEMICONDUCTOR  
PRODUCTION EXHAUST GASES

**REQUEST TO CORRECT TITLE OF INVENTION**

MAIL STOP ISSUE FEE  
COMMISSIONER FOR PATENTS  
P.O. BOX 1450  
ALEXANDRIA, VA 22313-1450

SIR:

In the matter of the above-identified application for patent, we hereby request  
correction of your records to reflect the correct title of the invention. The title of the  
invention should read as follows: **PROCESS AND APPARATUS FOR TREATING  
SEMICONDUCTOR PRODUCTION EXHAUST GASES.**

Respectfully Submitted,

OBLON, SPIVAK, McCLELLAND,  
MAIER & NEUSTADT, P.C.  
Norman F. Oblon



Vincent K. Shier, Ph.D.  
Registration No. 50,552

Customer Number

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(OSMMN 05/04)

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Surinder Sachar  
Registration No. 34,423

Docket No.: 0160-0193-0 PCT/hyc



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EXAMINER: Wayne A. LANGEL

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PRODUCTION EXHAUST GASES

**REQUEST TO CORRECT FILING DATE**

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COMMISSIONER FOR PATENTS  
P.O. BOX 1450  
ALEXANDRIA, VA 22313-1450

SIR:

In the matter of the above-identified application, we hereby request correction of your records to reflect the correct filing date of the invention. The correct filing date of the invention should be: **March 9, 2000**, as evidenced by the copy of the date-stamped filing receipt.

Respectfully Submitted,

OBLON, SPIVAK, McCLELLAND,  
MAIER & NEUSTADT, P.C.  
Norman F. Oblon

Vincent K. Shier, Ph.D.  
Registration No. 50,552

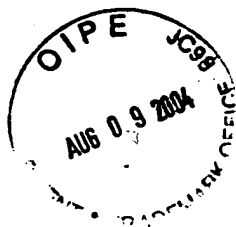
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O.S.&M. File No. 0160-0193-0 PCT B y NFO/dtv FF

Due Date NONE

Serial No. 09/463,961

In the Matter of the Application of Hiroshi IKEDA, et al.

**For PROCESS AND APPARATUS FOR TREATING**  
**SEMICONDUCTOR PRODUCTION EXHAUST GASES**

The following has been received in the U.S. Patent Office on the date stamped hereon:

- ☐      pps. Specification &      Claims (English Translation)
- ☒ Combined Declaration, Petition & Power of Attorney (3 pages)
- ☒ Submission of Declaration under 37 CFR 1.495
- ☒ PCT Transmittal Letter
- ☐ Verified Statement (Declaration) Claiming Small Entity Status
- ☐ Submission of Verified Statement (Declaration) Claiming Small Entity Status
- ☐ Check for \$                     ; ☒ Dep. Acct. Order Form
- ☐ Declaration of
- ☐ Assignment            pages/PTO-1595
- ☐ Letter to Official Draftsman
- ☐ Letter Requesting Approval of Drawing Changes
- ☐ Drawings      sheets
- ☒ Preliminary Amendment
- ☐ Information Disclosure Statement; ☐ PTO-1449
- ☐ Cited References (      )
- ☐                      Search Report
- ☐ Statement of Relevancy
- ☐ Restriction Response ☐ Election Response
- ☐ Rule 132 Declaration
- ☐ Petition
- ☐ Notice of Appeal

**95 Rec'd PCT/PTO 09 MAR 2000**  
Date Rec'd